



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Application of

Katsumi Maeda et al.

Serial No.: 09/750,116

Group Art Unit: 6329

Filed: December 29, 2000

Examiner: Rosemary E. Ashton

For: (METH) ACRYLATE DERIVATIVE, POLYMER AND PHOTORESIST
COMPOSITION HAVING LACTONE STRUCTURE, AND METHOD FOR
FORMING PATTERN BY USING IT

Honorable Commissioner of Patents
Washington, D.C. 20231

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APR 4 2003

TC 1700

Sir:

In response to the Office Action dated December 4, 2002, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please amend the Specification to read as follows:

On page 1, line 1, before "TECHNICAL FIELD" please insert:

a1
This is a continuation of International Application PCT/JP99/03580, which has an international filing date of July 2, 1999, was not published in English under PCT Article 21(2), and is now abandoned.

IN THE CLAIMS:

Please amend the claims to read as follows:

a2
2. (Amended) A polymer which is obtained by polymerizing the (meth) acrylate derivative according to claim 1, or copolymerizing the (meth) acrylate derivative according to claim 1 with another polymerizable compound.

a3
4. (Amended) A photoresist material comprising:
the polymer according to claim 2; and